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Erratum: “Measurement of the hot electron attenuation length of copper” [Appl. Phys. Lett. 96, 062105 (2010)]

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This article was originally published online and in print with these following mistakes:

(1) The address for authors L. Zhao and I. Appelbaum incorrectly appears in the footnote as “Present address.” The address should appear under the authors’ names to properly indicate their affiliation. In addition, the following text should be added to their departmental affiliation: *and Center for Nanophysics and Advanced Materials*.

- (2) To clarify, N_a was utilized to describe the doping density of the wafer which indicates the *arsenic* density not the *acceptor* density.
- (3) The width of the tunneling distribution is described as less than 7 meV. It should be less than 70 meV.

These mistakes do not change the results or conclusions of the paper. The corresponding author takes responsibility for these mistakes.

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